

## **Patent Assignment Abstract of Title**

## Total Assignments: 1

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**Inventor:** Hiroshi Nogami

**Title:** Method of cleaning CVD device

## Assignment: 1

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03/13/2002

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**Conveyance: Assignment of Assignors Interest (See Document for Details).**

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**Assignee:** ANELVA CORPORATION

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Search Results as of: 6/13/2003 1:55:32 P M

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Web interface last modified: Oct. 5, 2002

## WEST Search History

DATE: Friday, June 13, 2003

<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
		result set	
<i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L9	L6 and (He or Ar or Ne or Kr or Xe)	63	L9
L8	L6 same (He or Ar or Ne or Kr or Xe)	6	L8
L7	L6 and 15	62	L7
L6	(CVD or chamber or vessel) same clean\$3 same (oxygen with fluor\$3) ((134/1.1  134/21  134/22.1 )!.CCLS.  (216/63  216/64  216/67 !).CCLS.  (204/298.01 )!.CCLS.  (438/905 )!.CCLS.  (156/345.29  156/345.35  156/345.47 )!.CCLS. )	206	L6
<i>DB=JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ</i>			
L4	L1 and chemical vapor deposition	0	L4
L3	L1 and clean\$3	5	L3
L2	L1 and CVD	0	L2
L1	nogami-hiroshi\$.in.	108	L1

END OF SEARCH HISTORY